

1/18

FIG. 1A

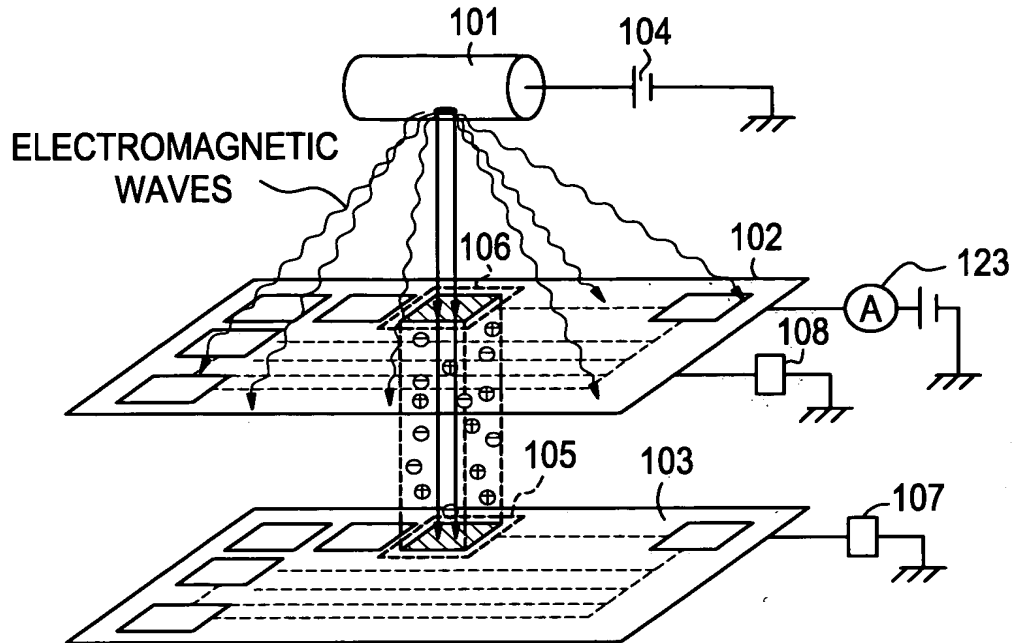


FIG. 1B

ENLARGED DIAGRAM OF 105

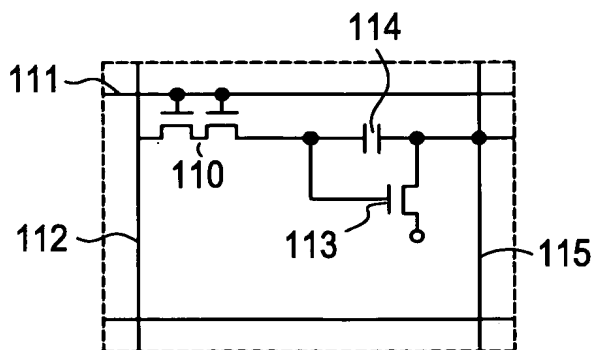
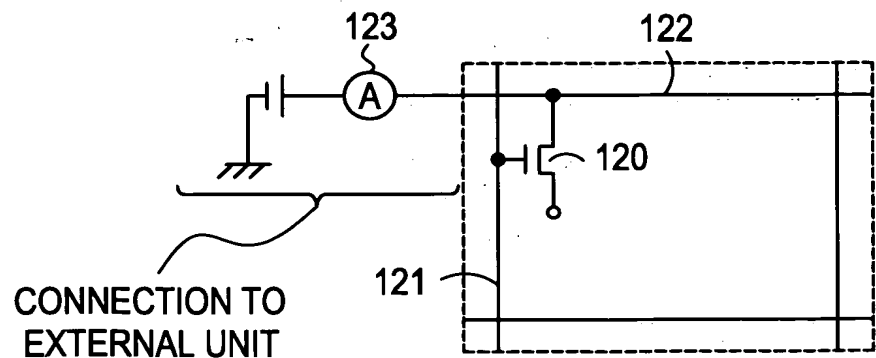


FIG. 1C

ENLARGED DIAGRAM OF 106



2/18

FIG. 2A

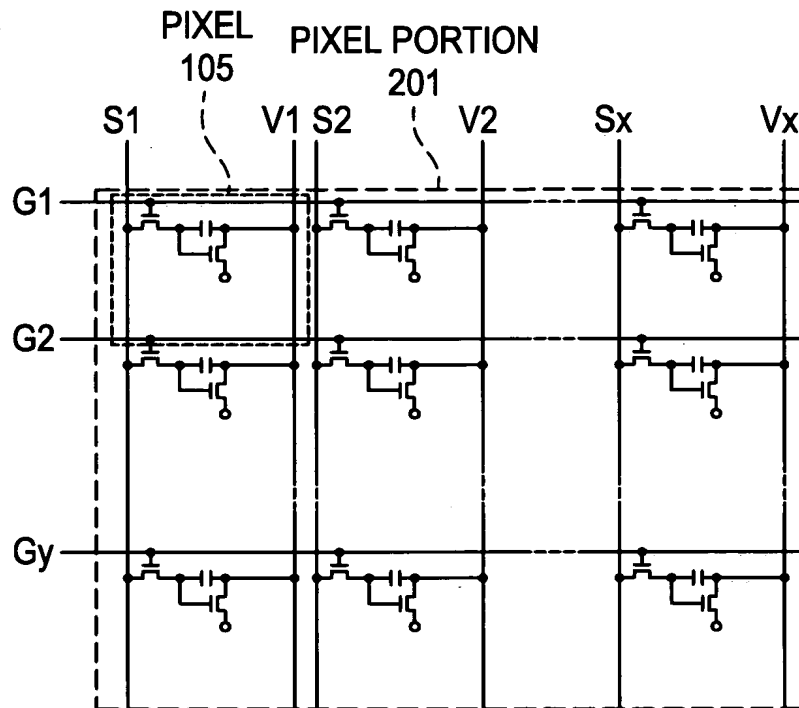
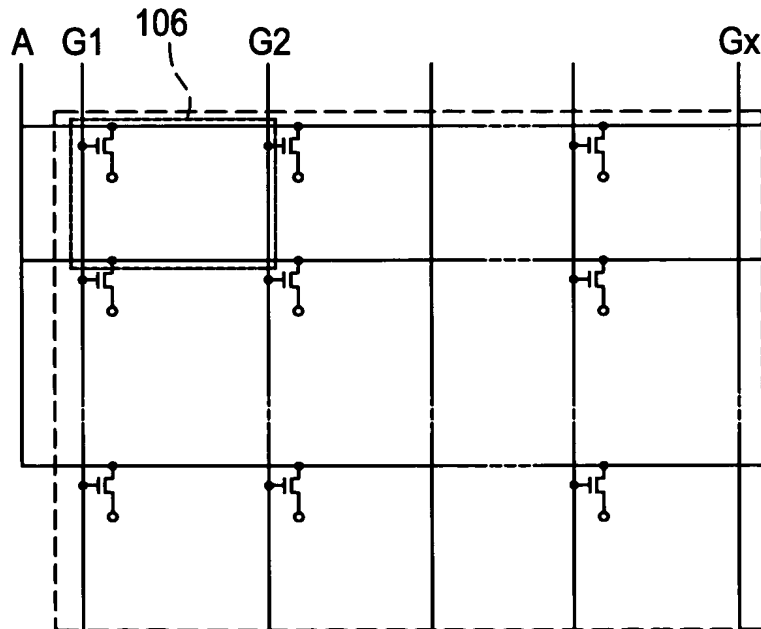


FIG. 2B

OPPOSING PORTION





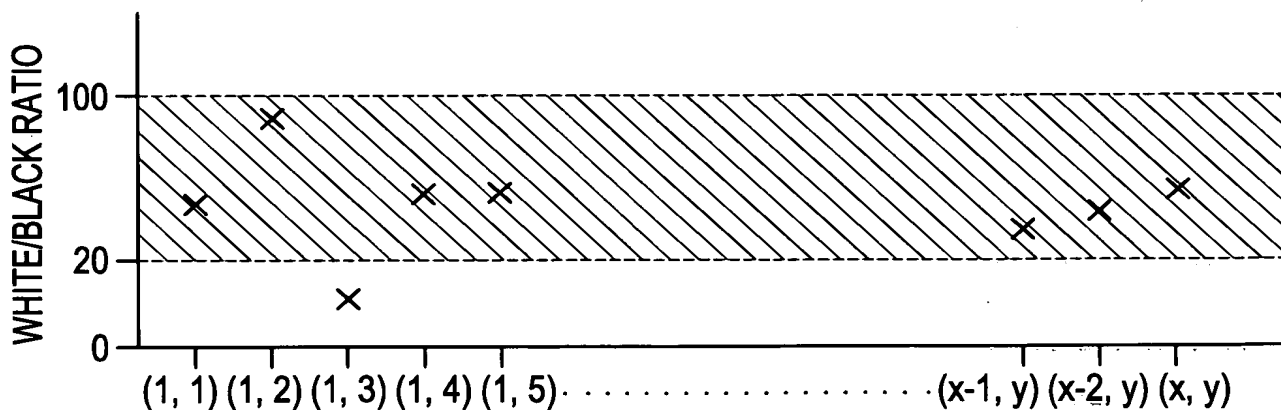
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3/18

FIG. 3A

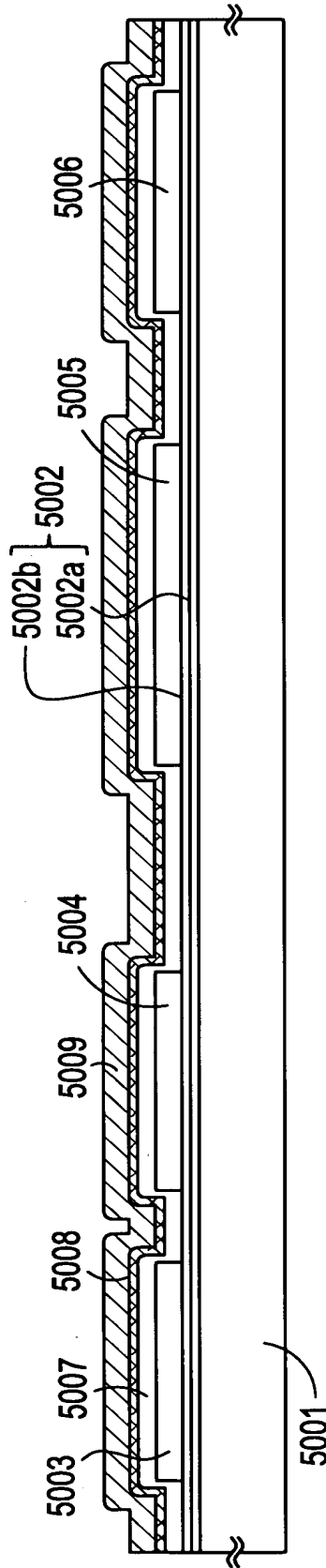
(1, 1)	(2, 1)	(3, 1)	(4, 1)		(x-1, 1)	(x, 1)
(1, 2)	(2, 2)	(3, 2)	(4, 2)		(x-1, 2)	(x, 2)
(1, 3)	(2, 3)	(3, 3)	(4, 3)		(x-1, 3)	(x, 3)
(1, 4)	(2, 4)	(3, 4)	(4, 4)		(x-1, 4)	(x, 4)
(1, y-1)	(2, y-1)	(3, y-1)	(4, y-1)		(x-1, y-1)	(x, y-1)
(1, y)	(2, y)	(3, y)	(4, y)		(x-1, y)	(x, y)

FIG. 3B



**FIG. 4A**

FORMATION OF ISLAND SEMICONDUCTOR LAYER, GATE-INSULATING FILM,  
AND FIRST AND SECOND CONDUCTING FILMS FOR GATE ELECTRODES



**FIG. 4B**

FIRST ETCHING AND FIRST DOPING

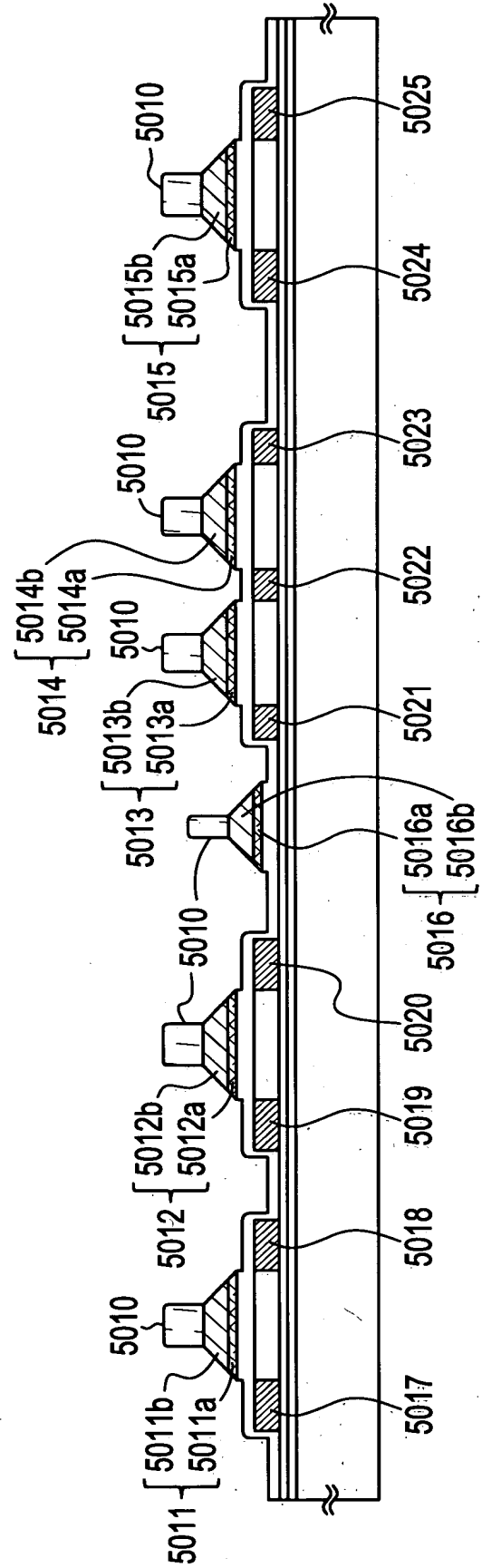
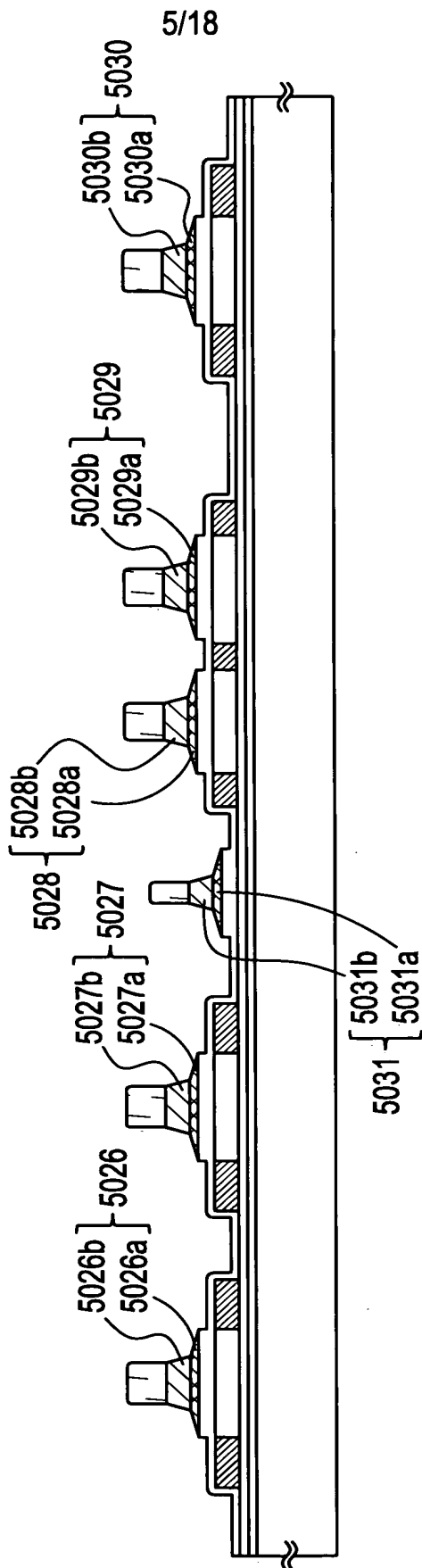
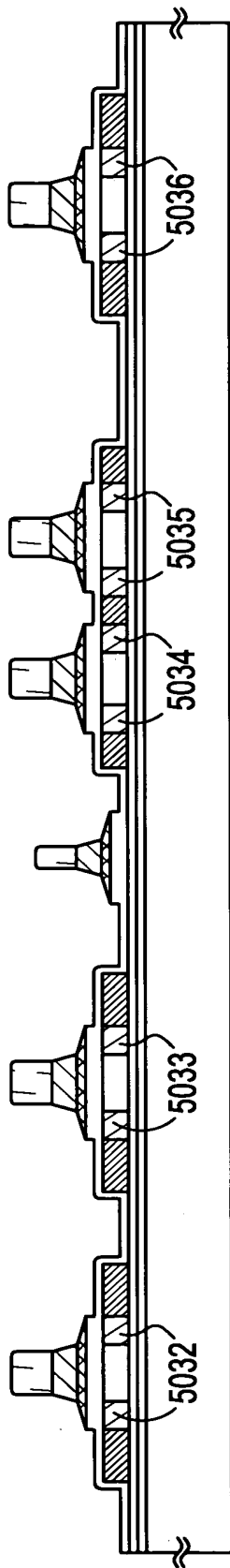


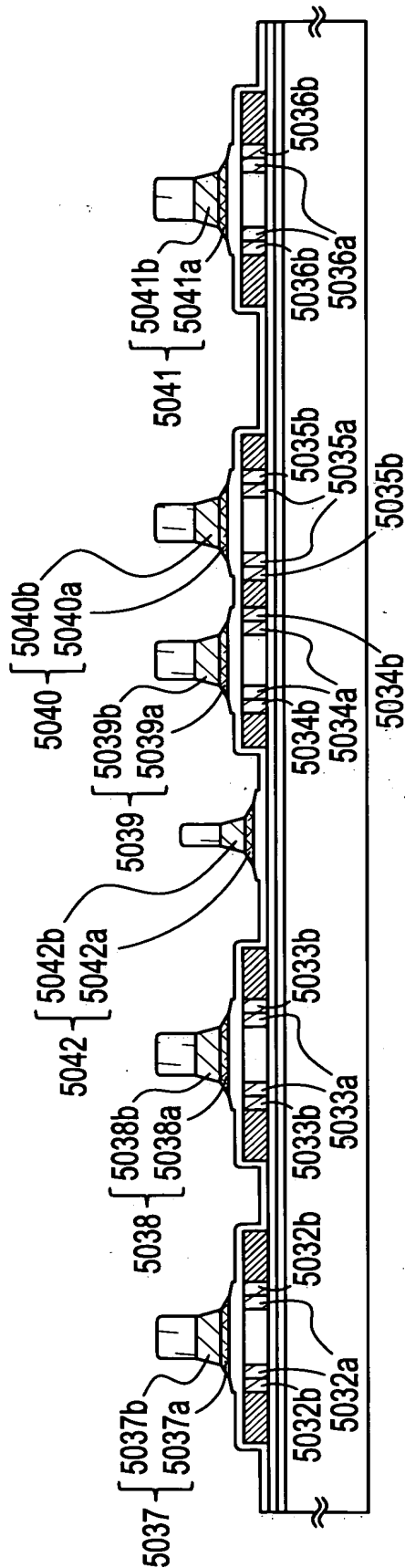
FIG. 4C  
SECOND ETCHING



**FIG. 5A**  
SECOND DOPING



**FIG. 5B**  
THIRD ETCHING



7/18

FIG. 5C  
THIRD DOPING

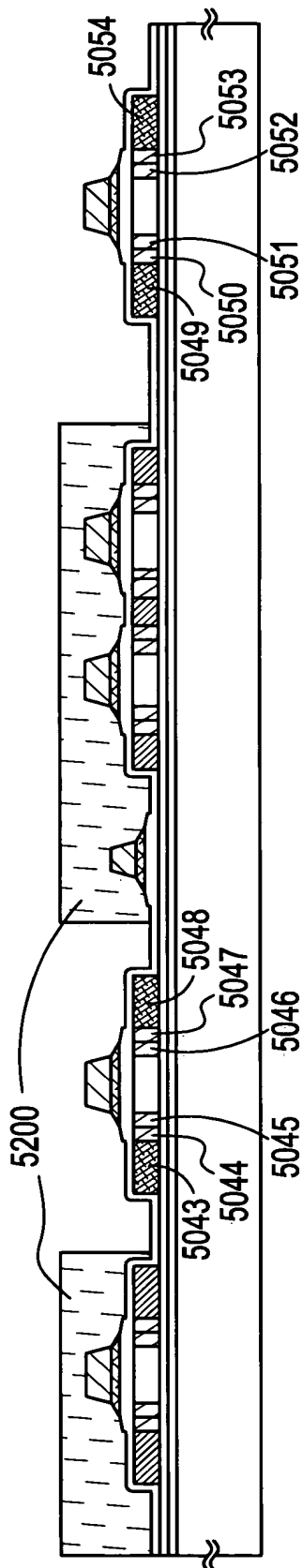


FIG. 6A

FORMATION OF THE FIRST AND SECOND INTERLAYER-INSULATING FILMS, WIRINGS AND PIXEL ELECTRODES

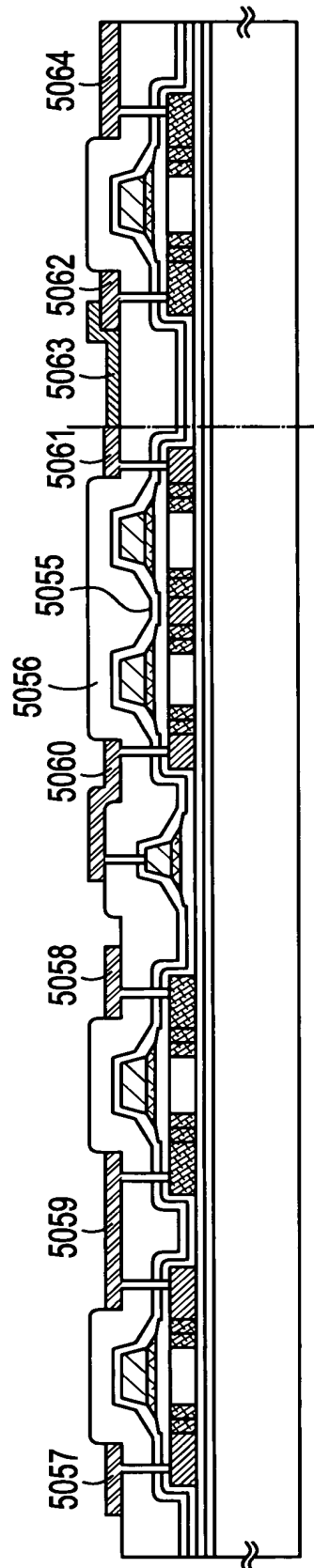
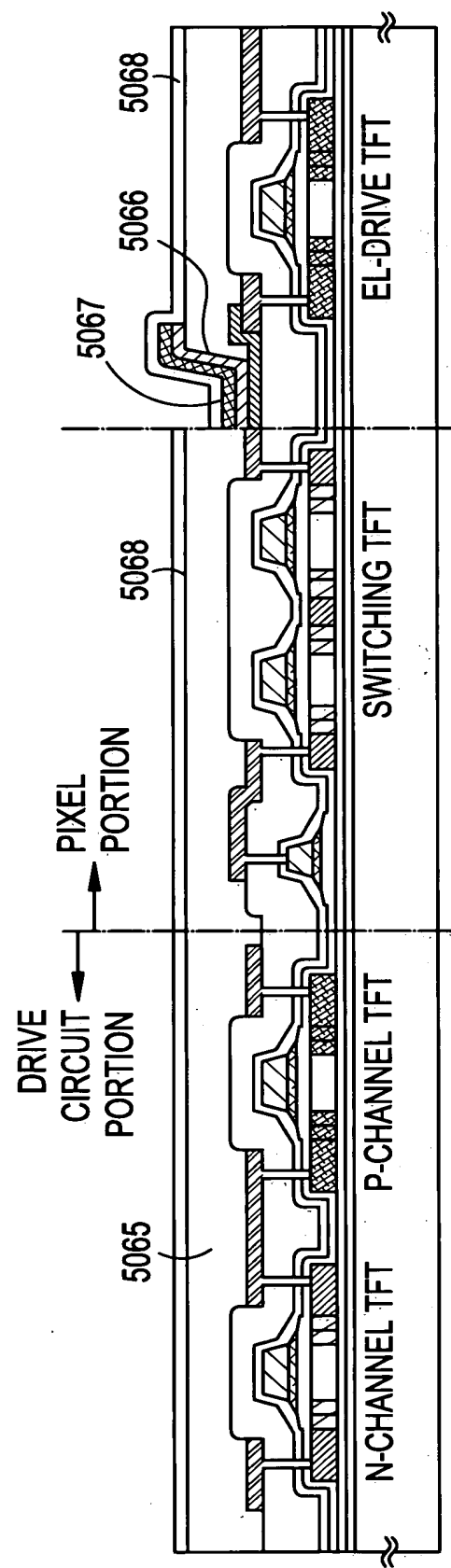


FIG. 6B

FORMATION OF THE THIRD INTERLAYER-INSULATING FILM, EL LAYER, CATHODES AND PASSIVATION FILM





9/18

FIG. 7A

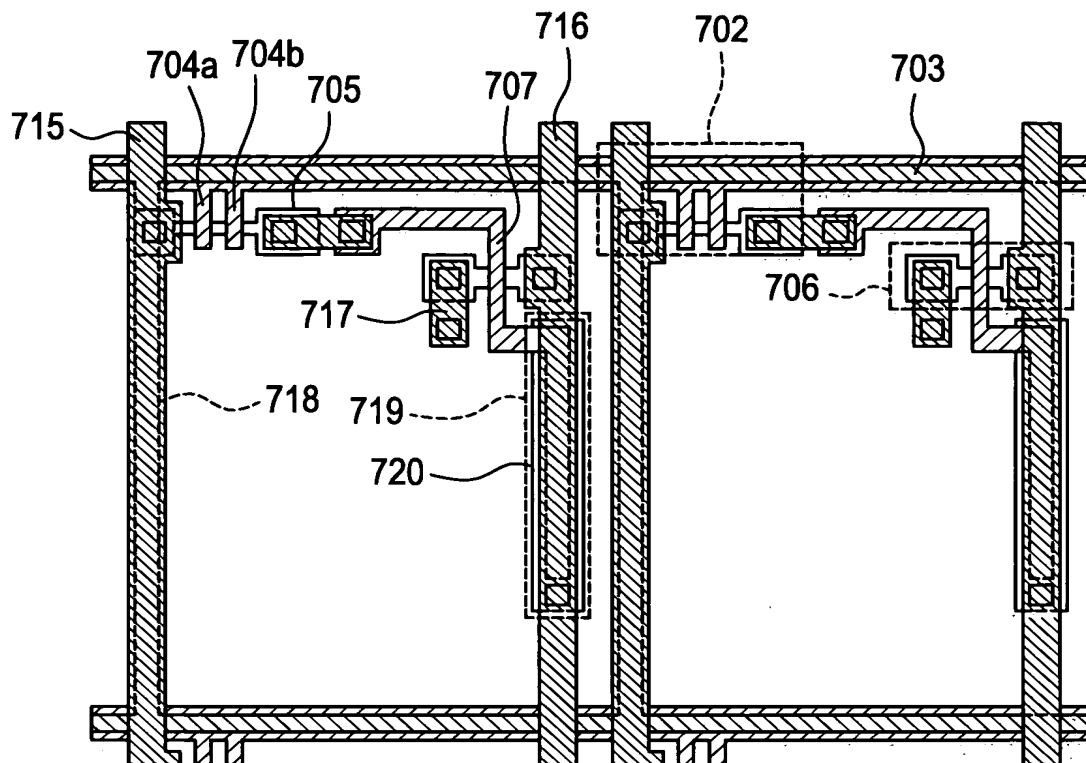
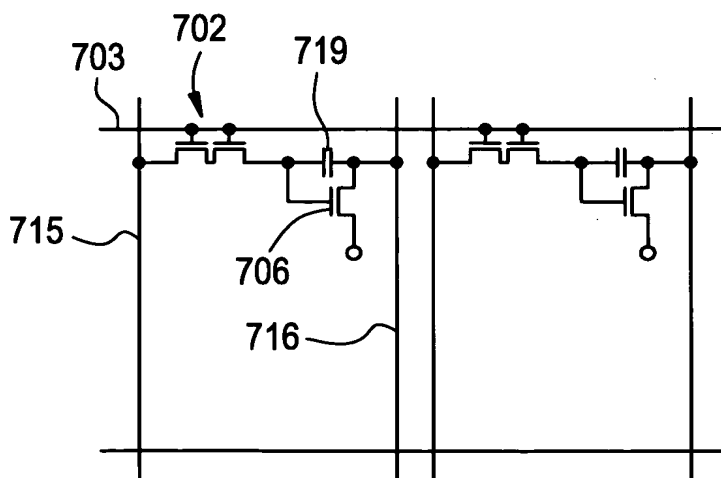


FIG. 7B



10/18

FIG. 8A

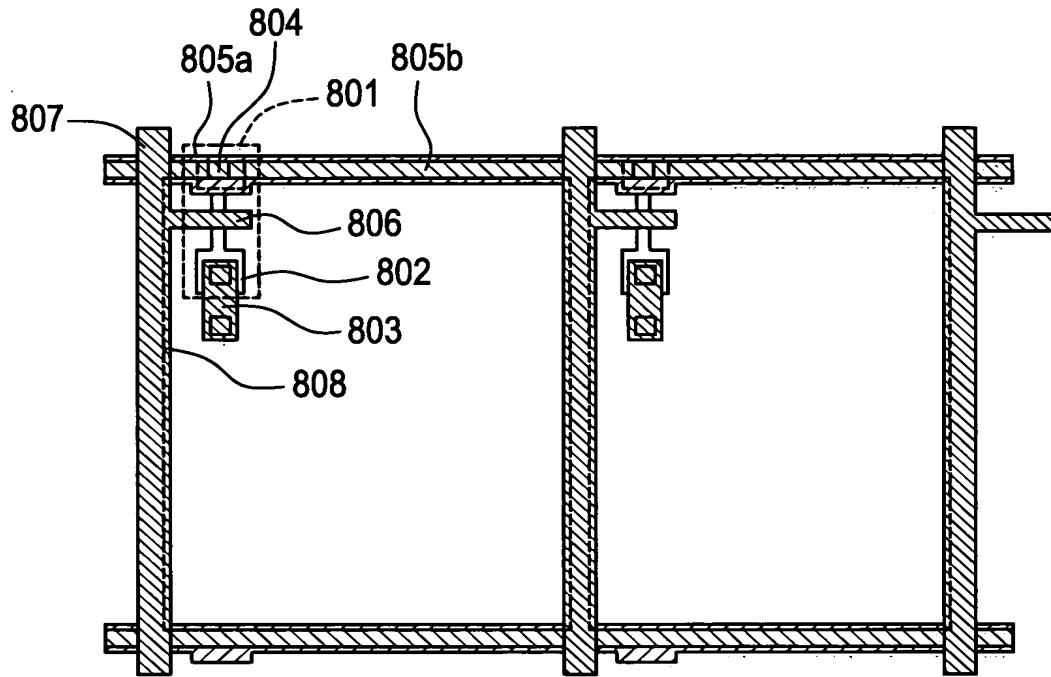


FIG. 8B

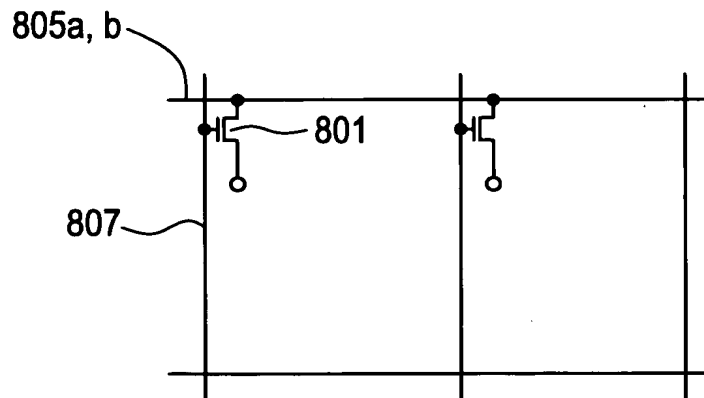
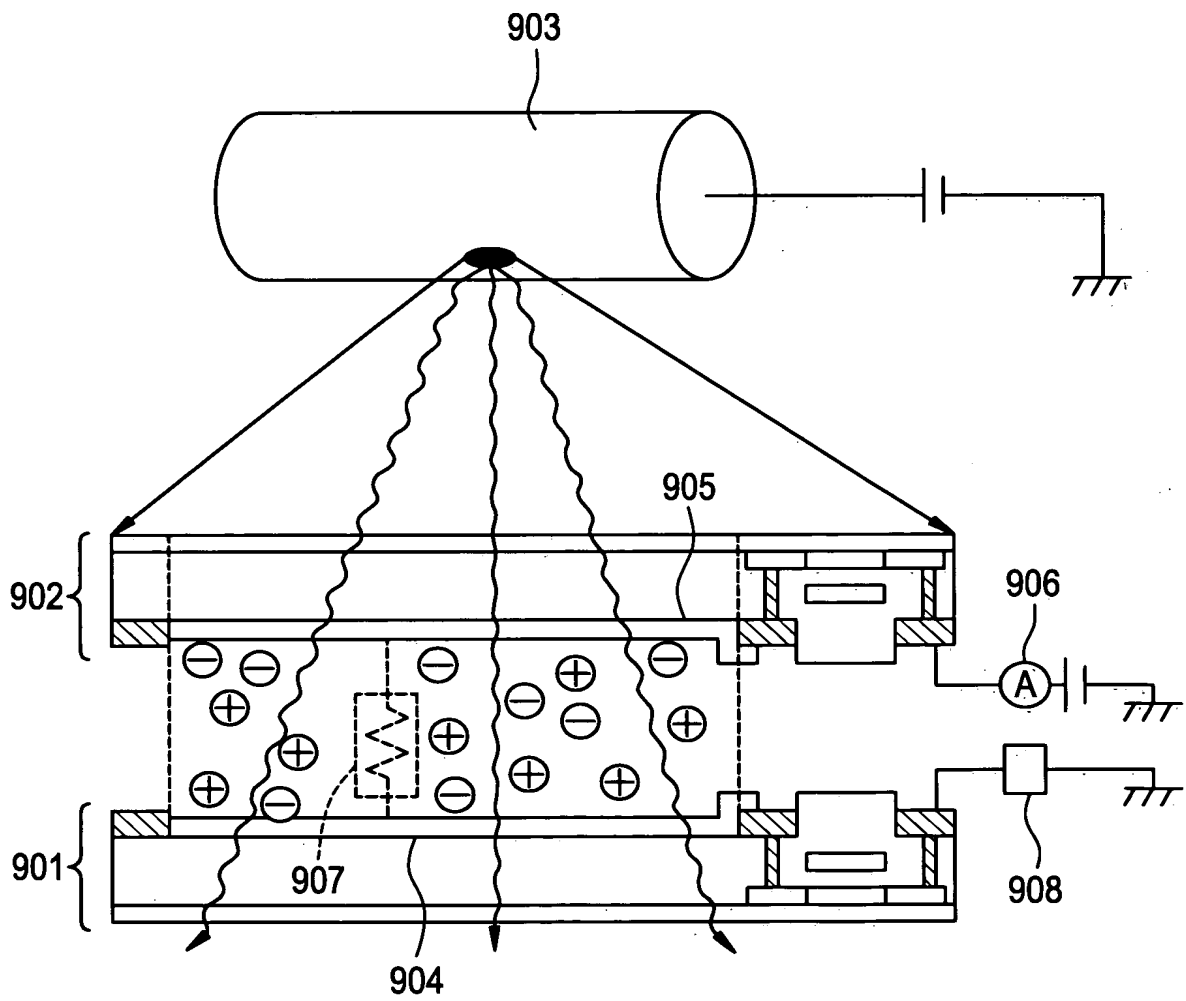


FIG. 9



12/18

FIG. 10

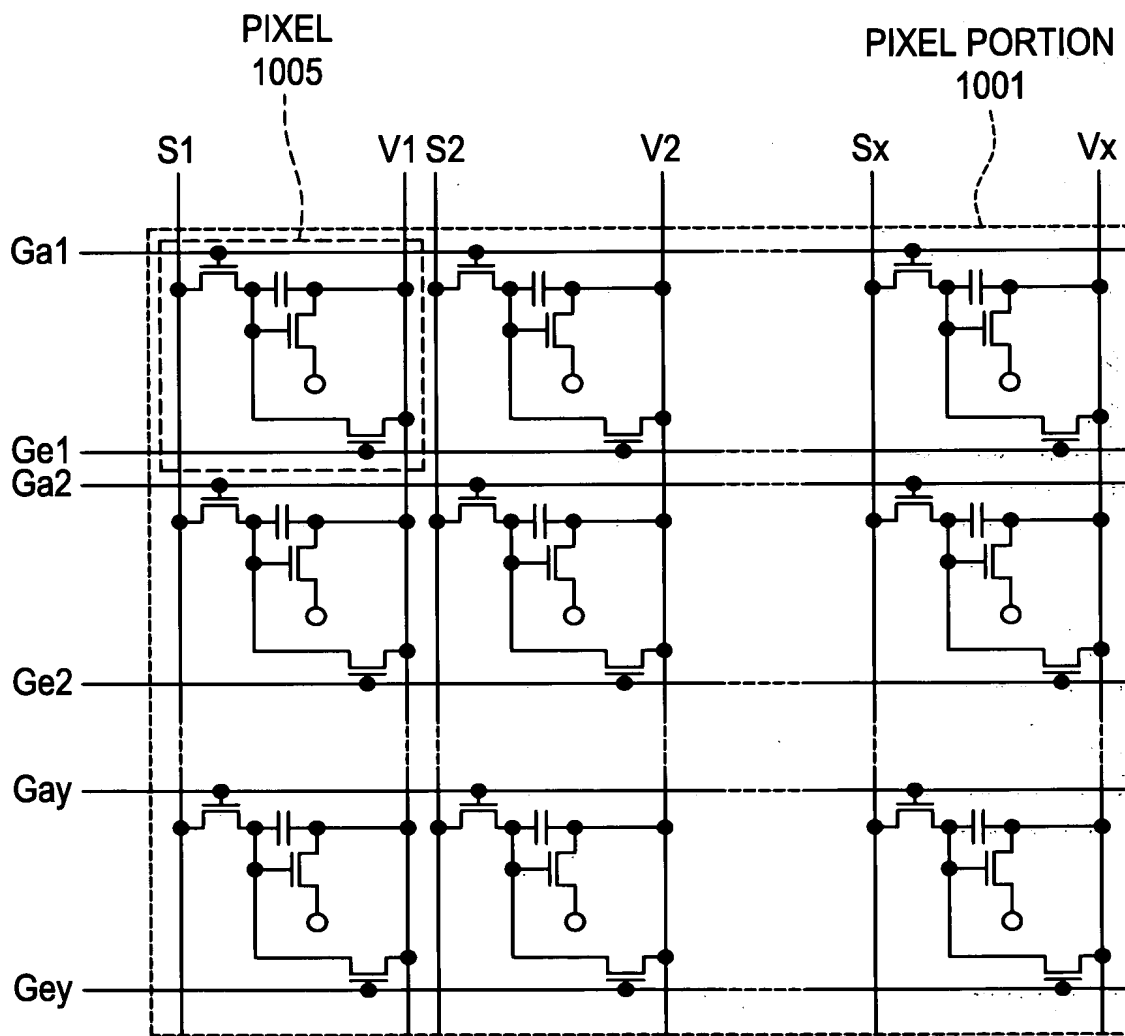


FIG. 11

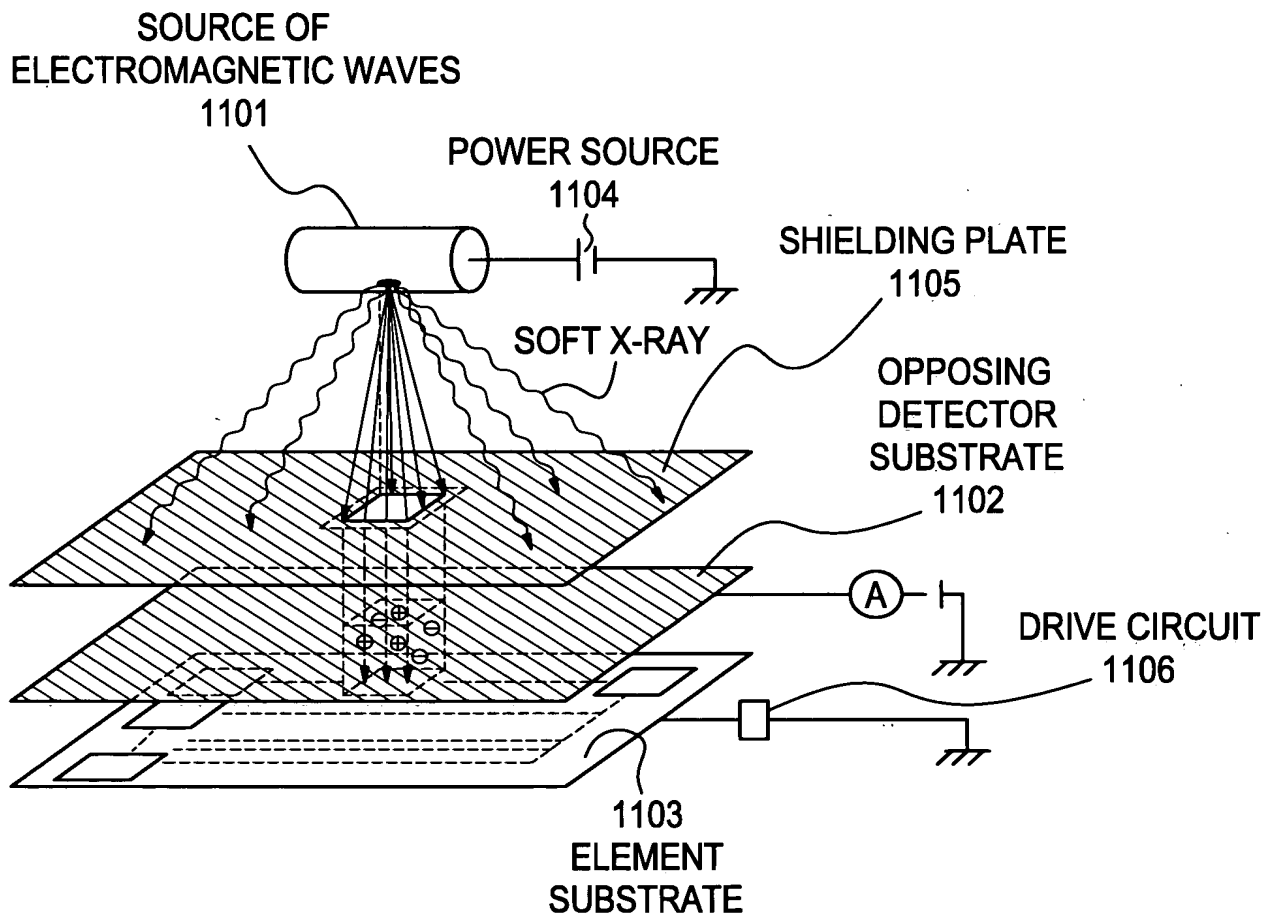


FIG. 12

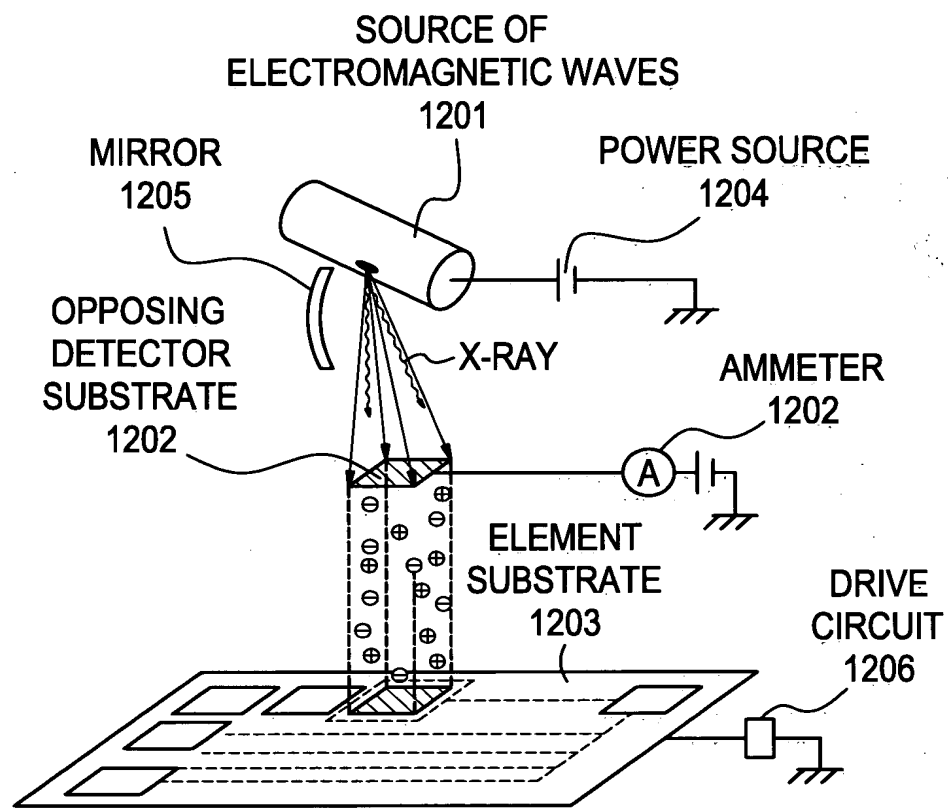


FIG. 13A

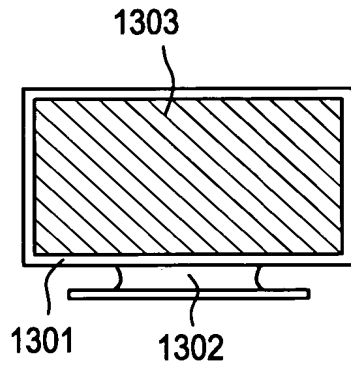


FIG. 13B

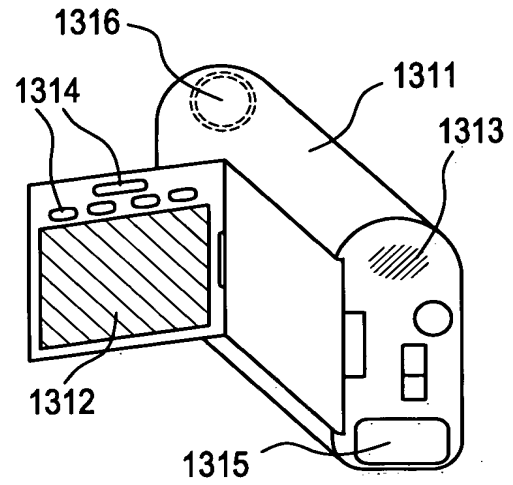


FIG. 13C

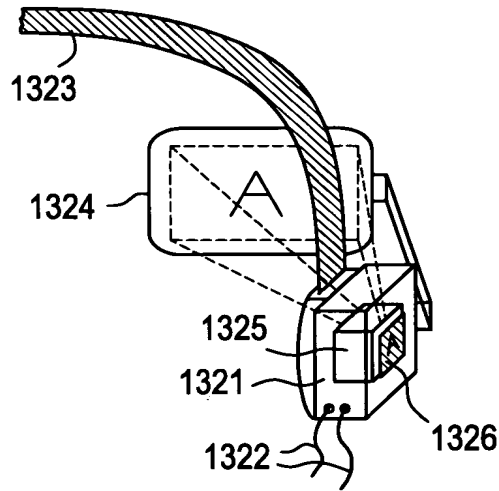


FIG. 13D

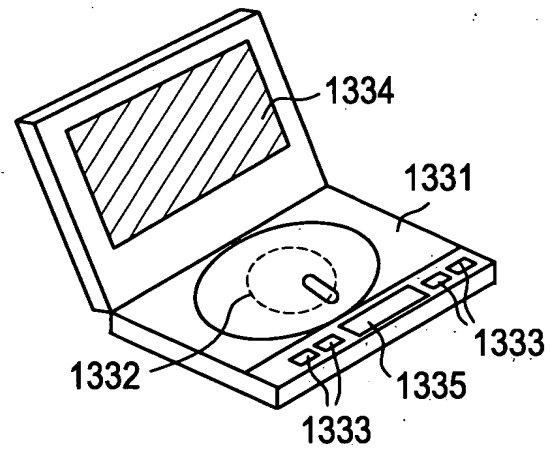


FIG. 13E

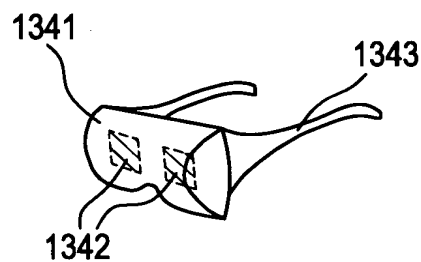
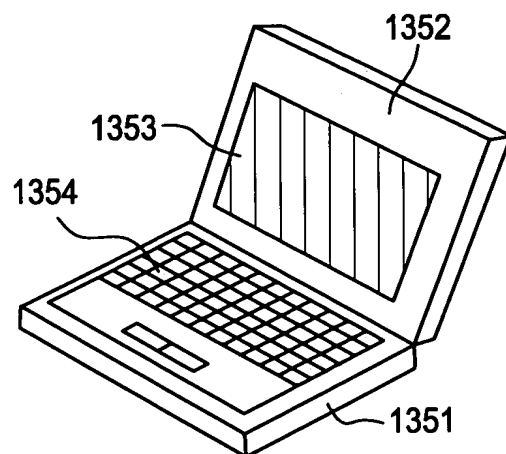


FIG. 13F



16/18

FIG. 14A

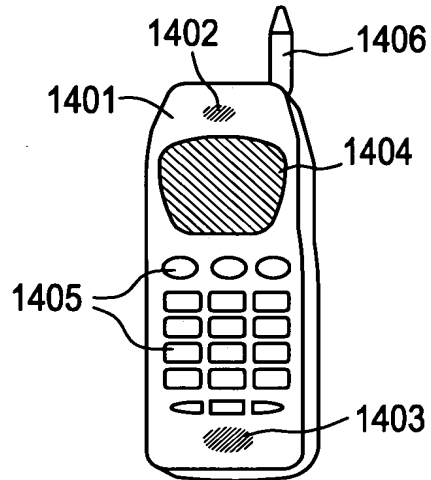


FIG. 14B

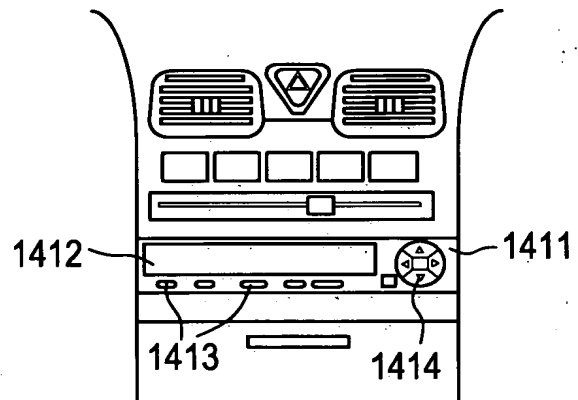


FIG. 14C

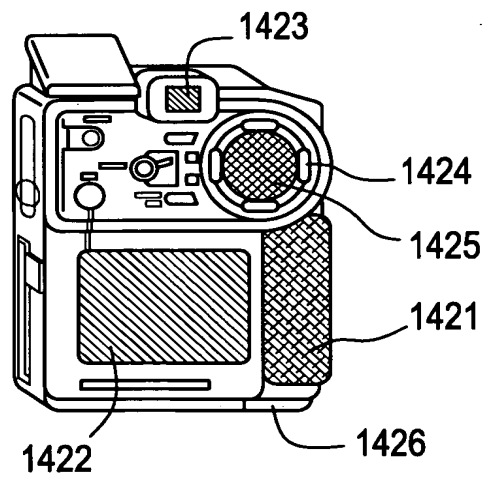
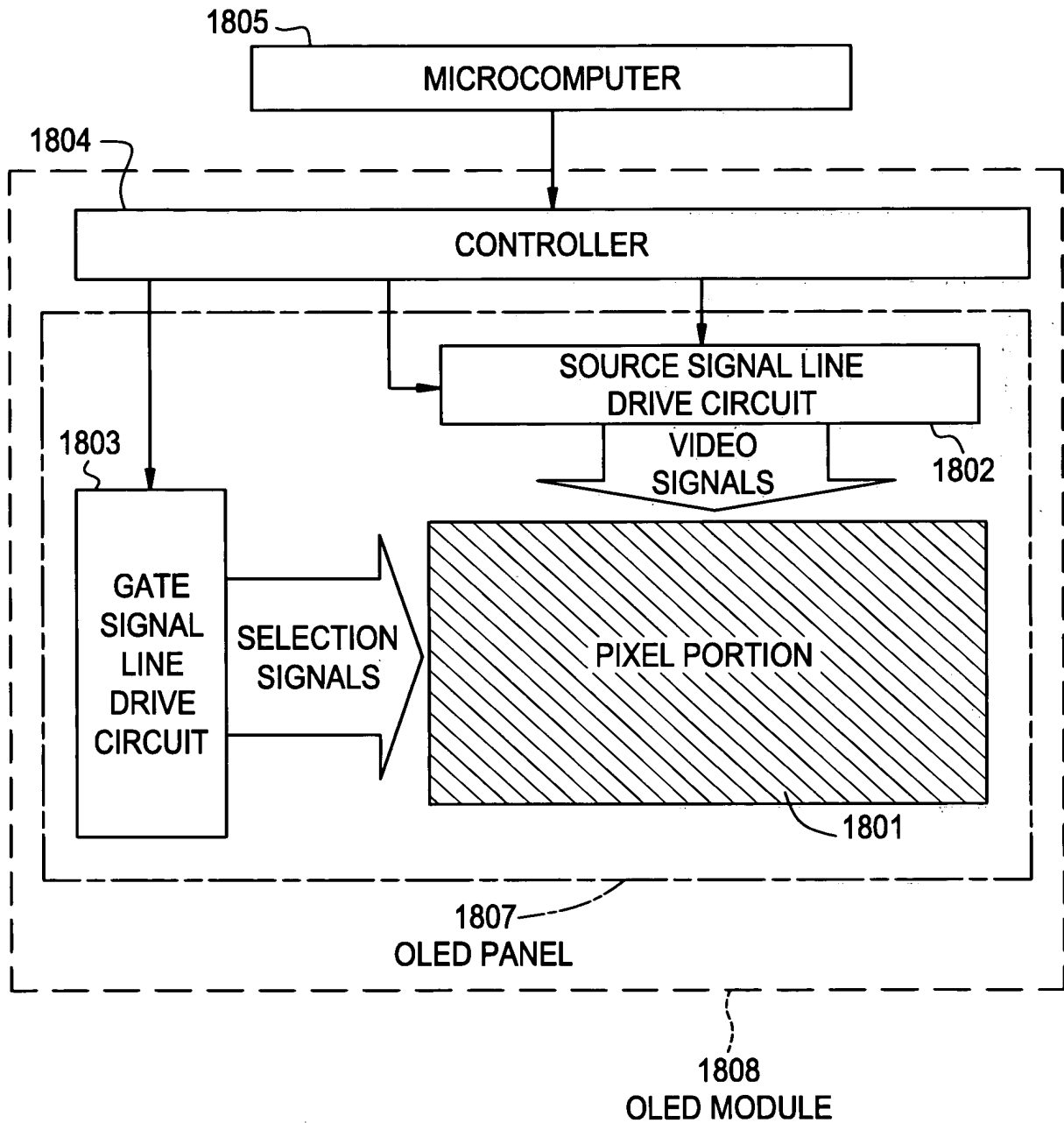




FIG. 15



18/18

FIG. 16A

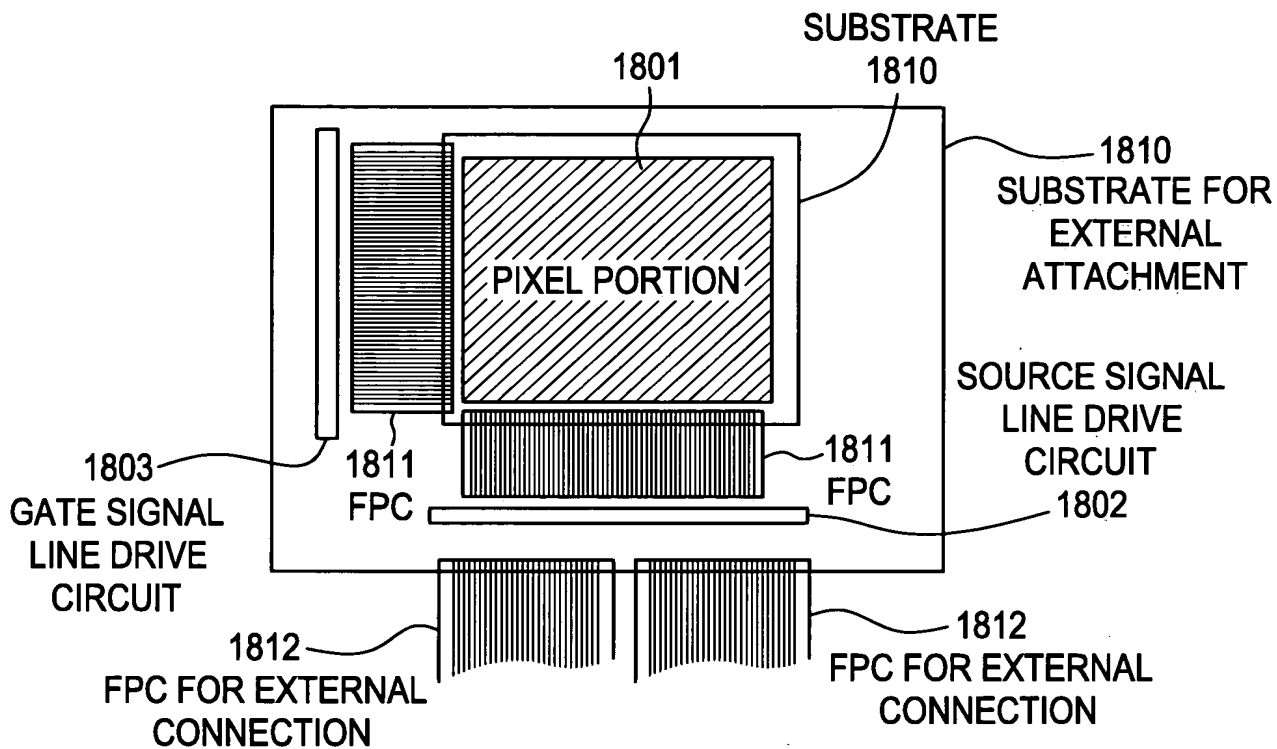


FIG. 16B

